

REMARKS

The statement in the outstanding Office Action that claims 30- 32 are allowed is appreciated.

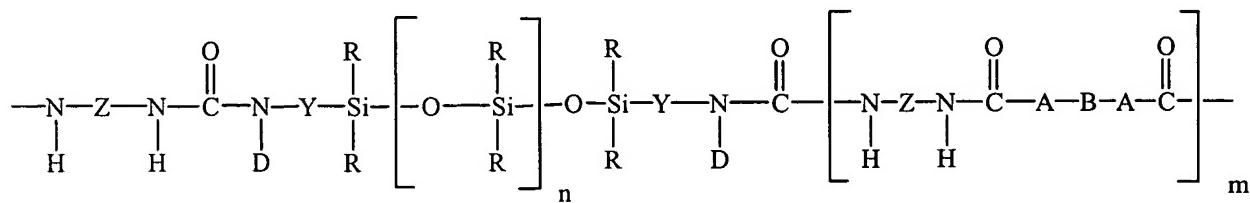
Prior Art-Based Rejections

The outstanding Office Action includes two prior art-based rejections. Claims 1-6, 8-14, 16-26, 29, and 33-38 stand rejected under 35 U.S.C. §102(b) over EP 380 236 (*Leir*). Claims 7, 15, 27, and 28 stand rejected under 35 U.S.C. §103(a) over *Leir*. These rejections are traversed.

Leir describes organopolysiloxane-polyurea block copolymers having the conventional excellent physical properties associated with polysiloxanes. See *Leir* at page 2, lines 49-53. *Leir* additionally describes the organopolysiloxane-polyurea block copolymers as useful as pressure sensitive adhesive compositions when tackified with a compatible tackifier resin. See *Leir* at page 3, lines 1-3.

The organopolysiloxane-polyurea block copolymers disclosed by *Leir*, however, fail to include the electron rich groups of the polydiorganosiloxane polyurea copolymer provided by the present invention. The electron rich groups of the polydiorganosiloxane polyurea copolymer of the present invention are selected from the group consisting of tertiary amine groups, pyridine groups, and combinations thereof.

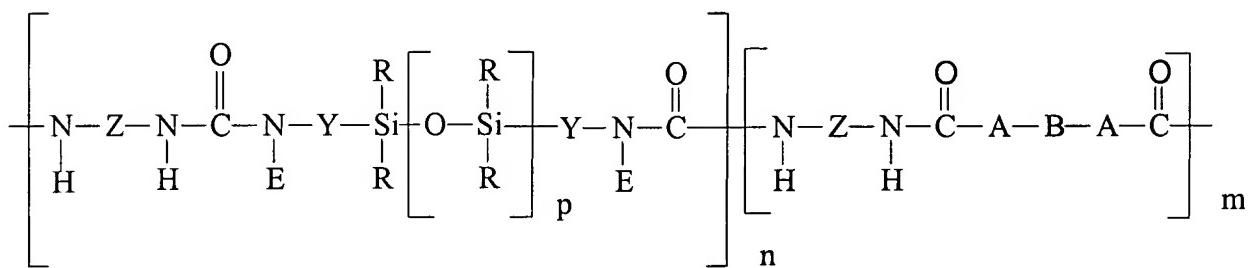
The structural representation of the organopolysiloxane-polyurea block copolymers disclosed by *Leir* at page 3, line 15 is provided below:



The substituents are disclosed by *Leir* at pages 3, lines 22-39. Although the structural formula of the organopolysiloxane-polyurea block copolymer disclosed by *Lier* appears similar to the structural formula of the polydiorganosiloxane polyurea copolymers disclosed by the above-identified patent application at page 6, line 1, there are differences. In particular, the

organopolysiloxane-polyurea block copolymers disclosed by *Leir* do not include the electron rich groups according to the present invention. According to *Leir*, the group "B" is "selected from the group consisting of alkylene, aralkylene, cycloalkylene, phenylene, polyethylene oxide, polypropylene oxide, polytetramethylene oxide, polyethylene adipate, polycaprolactone, polybutadiene, and mixtures thereof, and a radical completing a ring structure including A to form a heterocycle." See *Leir* at page 3, lines 30-32.

By way of comparison, the polydiorganosiloxane polyurea copolymer structure identified by the above-identified patent application at page 6, line 1, is provided below:



According to the above-identified application at page 7, lines 9-14, the group "B" is "an alkylene, aralkylene, cycloalkylene, phenylene, polyalkylene, polyalkylene oxide (including for example, polyethylene oxide, polypropylene oxide, polytetramethylene oxide, polycaprolactone, polyethylene adipate), copolymers, or mixtures thereof, or a moiety completing a ring structure including A to form a heterocycle; with the proviso that at least one B group includes an electron rich group (e.g. a tertiary amine or a pyridine group)." Clearly, the "proviso" is not disclosed or suggested by *Leir*.

Furthermore, the polydiorganosiloxane polyurea copolymer identified by independent claims 11, 13, and 25 require that the polydiorganosiloxane polyurea copolymer includes electron rich groups selected from the group consisting of tertiary amine groups, pyridine groups, and combinations thereof. This limitation is not disclosed or suggested by *Leir*. It is further pointed out that independent claim 33 provides that the polydiorganosiloxane polyurea copolymer comprise tertiary amine groups. This limitation is not disclosed or suggested by *Leir*.

It is pointed out that the Applicants were aware of *Leir*. In fact, *Leir* corresponds to U.S. Patent No. 5,461,134. This patent is identified and discussed in the above-identified patent application at, for example, page 1, lines 20-23, page 5, lines 24-30.

As described by the above-identified patent application at page 2, lines 7-14, the electron rich groups of the polydiorganosiloxane polyurea copolymer (the tertiary amine groups and/or pyridine groups) provide the composition with self-priming capability. As a result, there is no need for a secondary primer to adhere the compositions of the invention to certain substrates particularly those substrates containing electron poor groups such as acid-functional groups (e.g., carboxylic acid, sulphuric acid, and phosphoric acid groups). Accordingly, by providing a composition containing polydiorganosiloxane polyurea copolymers with electron rich groups according to the present invention, the Applicants provide a composition having self-priming properties.

In view of the failure by *Leir* to disclose an organopolysiloxane-polyurea block copolymer having electron rich groups selected from the group consisting of tertiary amine groups, pyridine groups, and combinations thereof, the claims are not anticipated by *Leir*. Furthermore, *Leir* fails to suggest modifying the disclosed organosiloxane-polyurea block copolymer to include electron rich groups selected from the group consisting of tertiary amine groups, pyridine groups, and combinations thereof.

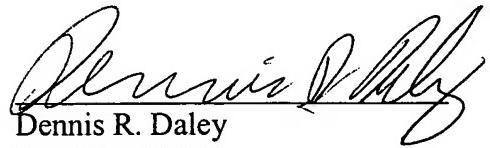
In view of the above comments, the claimed invention is not anticipated and would not have been obvious from *Leir*. Accordingly, withdrawal of the prior art-based rejections over *Leir* is requested.

It is believed that this application is in condition for allowance. Early notice to the effect is earnestly solicited.

Respectfully submitted,

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